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(54) METHOD OF PRODUCING A PRE-PATTERNED STRUCTURE FOR GROWING VERTICAL NANOSTRUCTURES

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(57)**ABSTRACT**

A method of producing a pre-patterned structure comprising at least one cavity for growing a vertical nanostructure is disclosed. The method includes providing at least one protruding structure that extends upwardly from a main surface of a substrate. The at least one protruding structure has a main portion of a first height and an upper portion on the main portion. The method also includes embedding the at least one protruding structure in a dielectric material. Further, the method includes removing at least an excess portion of the dielectric material, thereby exposing a top surface of the upper portion and forming a flattened surface of the top surface of the upper portion and the dielectric material. In addition, the method includes forming at least one cavity of a first depth by removing the upper portion, thereby exposing a top surface of the main portion of the at least one protruding structure.

